

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**
(Not for submission under 37 CFR 1.99)

Application Number	10518060
Filing Date	2005-06-09
First Named Inventor	Lutz Lehmann
Art Unit	1712
Examiner Name	Kua Liang Peng Robert Loewe
Attorney Docket Number	H26787.68596 US - 4780

U.S. PATENTS

Examiner Initial*	Cite No	Patent Number	Kind Code ¹	Issue Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
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	2	4299938		1981-11-10	Ciba-Geigy Corporation	
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	6	4863827		1989-09-05	American Hoechst Corporation	
	7	4910122		1999-03-20	Brewer Science, Inc.	
	8	4935583		1990-06-19	Kyle, James C.	

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11	5100503		1992-03-31	NCR Corporation	
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20	6472128	B2	2002-10-29	Shipley Company, L.L.C.	
21	6528235	B2	2003-02-04	Shipley Company, L.L.C.	
22	5674648	A	1997-10-07	Brewer et al.	
23	4191571		1980-03-04	Nonogaki et al.	

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U.S. PATENT APPLICATION PUBLICATIONS

Examiner Initial*	Cite No	Publication Number	Kind Code ¹	Publication Date	Name of Patentee or Applicant of cited Document	Pages, Columns, Lines where Relevant Passages or Relevant Figures Appear
	1	20060110682	A1	2006-05-25	Shipley Company, L.L.C.	
	2	20060155594	A1	2006-07-13	Jess Almeida, et al.	

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Application Number	10518060	10518060 - GAU: 1796
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Examiner Initials*	Cite No	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc), date, pages(s), volume-issue number(s), publisher, city and/or country where published.	T ⁵
	1	Grivello et al., J. Polym. Sci.: Polym. Chem. 21 (1983), 87-109.	<input type="checkbox"/>
	2	Degorce, "Science for Adhesives and Sealants," 18-19, available at www.dynasydan.com	<input type="checkbox"/>
	3	Lemels, A., et al., "Chemically Amplified Resists," Solid State Technology, 53-60 (August 1991).	<input type="checkbox"/>
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	5	McKean et al., "Characterization of a Novolac-Based Three-Component Deep-UV Resist," Chem. Mater. (1990) 2, 619-624.	<input type="checkbox"/>
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	7	Silverstein et al., "Spectrometric Identification of Organic Compounds," 4th Ed., John Wiley & Sons 1991, 309-311.	<input type="checkbox"/>
	8	Willson, C.G., "Organic Resist Materials - Theory and Chemistry," Introduction to Microlithography, American Chemical Society, 87-159 (1983).	<input type="checkbox"/>
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	10	"HD Micro Photo-Cut Positive Polyamide," Electronic News, June 19, 2000.	<input type="checkbox"/>

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11	Jaskot et al., "Toxicological Sciences, 22(1): 169-172 (1994).		<input type="checkbox"/>
12	Y.-C. Lin et al., "Some Aspects of Anti-Reflective Coating for Optical Lithography," Advances in Resist Technology and Processing, Proc., SPIE vol. 469, 30-37 (1984).		<input type="checkbox"/>
13	Brewer, T. et al., "The Reduction of the Standing Wave Effect in Positive Photoresists," Jour. Appl. Photogr. Eng., Vol. 7, no. 6, 184-186 (Dec. 1981).		<input type="checkbox"/>
14	Yusuke Izumi et al., "Hydrosilylation of Carbonyl Compounds Catalyzed by Solid Acids and Bases," Tetrahedron Letters, Vol. 32, No. 36, pp 4744 (1991).		<input type="checkbox"/>

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Examiner Signature	/Robert Loewe/	Date Considered	04/24/2008
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